

**OS1: The Eighth International Symposium on Innovative Energy Research I:
Advanced Materials and its Energy Application
&**

**OS3: The Eighth International Symposium on Innovative Energy Research III: Multiphase
Energy Science and Technology (Combination of Monozukuri-Fluid Science/Engineering)**

October 28, 2020
ROOM2 (Meet)

- OS1/3-1 **On Electron Energy Bands of Si / Si_{0.7}Ge_{0.3} Nanopillars**
9:20-9:40 Min-Hui Chuang, Yiming Li, Daisuke Ohori (National Chiao Tung University, Taiwan), Seiji Samukawa (Tohoku University, Japan)
- OS1/3-2 **On a Rotating Hollow Cylinder in Flight**
9:40-10:00 Mao Nagata (Doshisha University, Japan), Hirochika Tanigawa (Maizuru National College of Technology, Japan), Jun Ishimoto, Masami Nakano (Tohoku University, Japan), Takashi Noguchi, Katsuya Hirata (Doshisha University, Japan)
- OS1/3-3 **Visualization of Flow Pattern of Saturated Steam for Gas-Liquid Two-Phase Flow**
10:00-10:20 Shinichi Oki, Yoshiaki Tanzawa (Nippon Institute of Technology, Japan), Jun Ishimoto (Tohoku University, Japan)
- OS1/3-4 **Effect of Wood Species on the Hydrophobic Properties of Biofuel Obtained by Torrefaction**
10:20-10:40 Alexey Korshunov, Boris Kichatov, Alexey Kiverin (Lebedev Physical Institute, Russian Academy of Sciences, Russia)
- OS1/3-5 **Estimation of Multiple Coefficients to Express Longitudinal and Transverse Electrostriction in the PTMO Crystal**
11:10-11:30 Ai Suzuki, Masayuki Miyano, Ryuji Miura (Tohoku University, Japan), Gildas Diguët, Jean-Yves Cavaille, Gael Sebald (ELyTMaX UMI 3757, CNRS – Université de Lyon – Tohoku University, International Joint Unit, Tohoku University, Japan)
- OS1/3-6 **Inverse Magnetostrictive Properties for Magneto Stress-Impedance Characterization of Thin Films**
11:30-11:50 Gildas Diguët (Tohoku University / ELyTMaX UMI 3757, CNRS – Université de Lyon – Tohoku University, International Joint Unit, Tohoku University, Japan), Kei Makabe, Hiroki Kurita, Joerg Froemel, Fumio Narita (Tohoku University, Japan)
- OS1/3-7 **Numerical Simulation of H and CH₃ Distribution in the Deposition Chamber**
11:50-12:10 Zhang Yi Chi, Shen Qian Hao, Qi Hao Xuan, Zhai Ming (Harbin Institute of Technology, China)
- OS1/3-8 **Numerical Simulation of Microwave Chemical Vapor Deposition Chamber Reaction Process**
12:10-12:30 Zhang Yi Chi, Qi Hao Xuan, Shen Qian Hao, Zhai Ming (Harbin Institute of Technology, China)